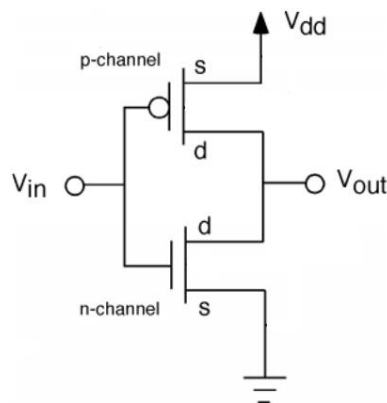


## EEE225 Solution Sheet 2 - NJP

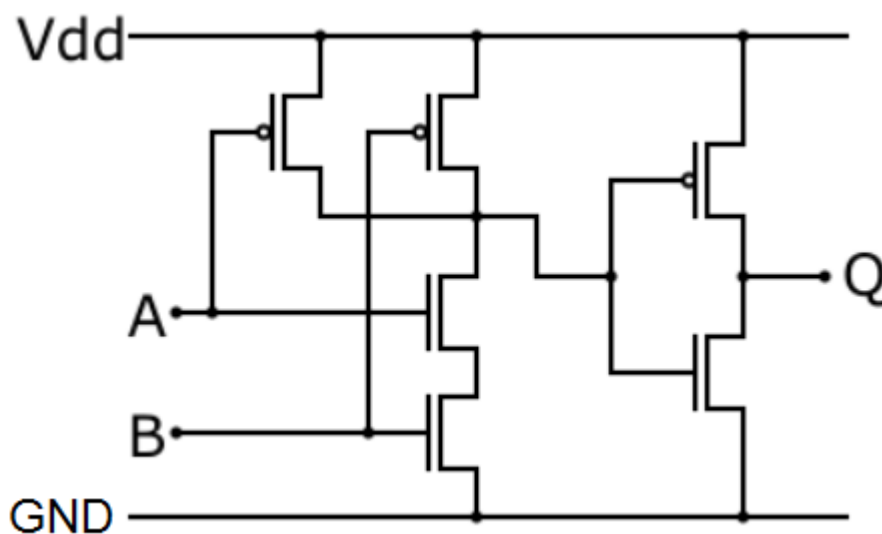
1. In modern CMOS technologies (65nm and below), gate leakage currents are the dominant source of leakage (> 90%). This occurs due to tunnelling through the thin gate oxide. Scaling of the technology results in thinner gate oxides further increasing the leakage due to tunnelling.
2. Noise Margin (High)  $4.4 - 3.15 = 1.25 \text{ V}$  , Noise Margin (Low)  $1.35 - 0.1 = 1.25 \text{ V}$ .
3. Hint: Draw the equivalent circuit with resistors, use  $V^2/R$  for power.



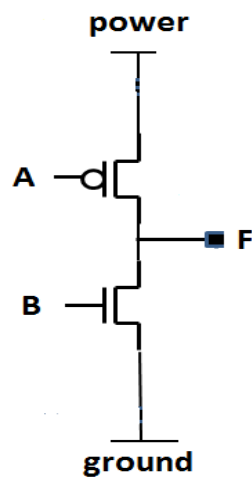
$$(i) V_{out} = 4.999\text{V} \quad P_{diss} = 0.05\text{mW}$$

$$(ii) V_{out} = 0.00025\text{V} \quad P_{diss} = 0.05\text{mW}$$

4. nmos: electrons majority carrier, pmos: holes majority carrier. Electrons have a higher mobility than holes, hence nmos has lower 'on' resistance.
5. Universal logic gates are NAND & NOR as they can be used to implement any Boolean logic function.
- 6.



7.



EN	IN	A	B
0	0	1	0
0	1	1	0
1	0	1	1
1	1	0	0

Remember, you want a buffer, not an inverter.

$$A = \overline{EN} \cdot \overline{IN} \quad B = EN \cdot \overline{IN} = \overline{\overline{EN} + IN} \quad (\text{use involution and De Morgan, circuit diagram is in your notes})$$

8.

EN	IN	A	B
0	0	1	1
0	1	0	0
1	0	1	0
1	1	1	0

$$B = \overline{\overline{EN} + IN}$$

$$A = \overline{\overline{EN} \cdot \overline{IN}} + EN \cdot \overline{IN} + EN \cdot IN = \overline{\overline{EN} \cdot \overline{IN}} + EN = EN + \overline{\overline{EN} \cdot \overline{IN}}$$

$$= \overline{\overline{EN} \cdot \overline{IN}}$$

9.

$$= EN \cdot IN$$

Hence, logic diagram.

Simplification Theorem :  $X + \overline{X}.Y = X + Y$  (I would not expect you to remember this theorem)